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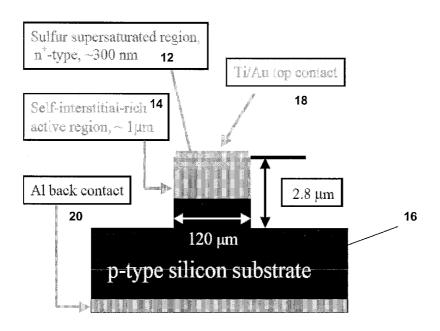
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#### (54) Title: A POINT DEFECT ENGINEERED SI LIGHT-EMITTING DIODE AT 1.218 $\mu M$



(57) Abstract: A light-emitting device (LED) includes a first semiconductor layer comprising of n-type dope materials. A second semiconductor layer includes p-type dope materials. An active region is positioned between the first and second semiconductor layers. The active region includes Si self-interstitials used in producing having electroluminescence wavelengths at emissions approximately 1.218 µm.



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C. DOCUMENTS CONSIDERED TO BE RELEVANT		
Category* Citation of document, with indication, v	where appropriate, of the relevant passages	Relevant to claim No.
	US 2005/0082543 A1 (ALIZADEH et al.) 21 April 2005 (21.04.2005) para [0006], [0014], [0041], [0043], [0045], [0048]-[0049], [0064], [0072], [0075]; See Figs. 1-3	
Y US 2003/0168665 A1 (KIM et al.) 11 September [0016], [0043], [0078] and [0080]; See Fig. 7	US 2003/0168665 A1 (KIM et al.) 11 September 2003 (11.09.2003) para [0011]-[0012], [0014], [0016], [0043], [0078] and [0080]; See Fig. 7	
Y US 2005/0111779 A1 (JOYNER et al.) 26 May [0047]-[0050] and [0076]	US 2005/0111779 A1 (JOYNER et al.) 26 May 2005 (26.05.2005) para [0021], [0024], [0029], [0047]-[0050] and [0076]	
A US 2004/0062284 A1 (JEWELL) 01 April 2004	US 2004/0062284 A1 (JEWELL) 01 April 2004 (01.04.2004)	
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